PATTERN FORMING APPARATUS AND PATTERN FORMING METHOD, MOVABLE BODY DRIVE SYSTEM AND MOVABLE BODY DRIVE METHOD, EXPOSURE APPARATUS AND EXPOSURE METHOD, AND DEVICE MANUFACTURING METHOD

ABSTRACT

An aerial image measuring apparatus is partially arranged on a wafer stage (WST), and the rest is partially arranged on a measuring stage (MST), and measures the aerial image of a mark formed by a projection optical system (PL). Thus, for instance, at the time of measuring the best focus position of the projection optical system (PL) by the aerial image measuring apparatus, measurement can be performed by having, as a reference of the best focus position, a position which relates to a direction parallel to the optical axis (AX) of the projection optical system of the wafer stage whereupon the aerial image measuring apparatus is partially arranged. Therefore, at the time of exposing an object (W) with illuminating light (IL), based on the measurement results of the best focus position, a position relating to a direction parallel to the optical axis (AX) of the wafer stage (WST) is adjusted at high precision

Figure 1